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Article

Tunable Iron–Cobalt Thin Films Grown by Electrodeposition

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Citation: Gon, S.; Andrade, V.; Célia T. Sousa; João P. Araújo; João H. Bel Tunable Iron–Cobalt Thin Films Grown by Electrodeposition. *Magnetochemistry* **2023**, *9*, 161. https://doi.org/10.3390/magnetochemistry9070161

Received: 29 April 2023
Revised: 31 May 2023
Accepted: 17 June 2023
Published: 21 June 2023

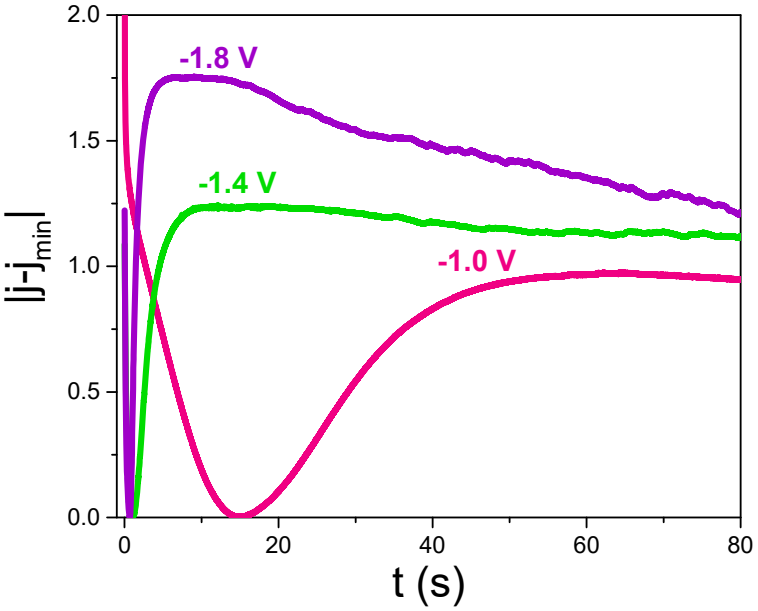

Figure S1. Overall j-j_{min} as a function of time to illustrate that the t_{max} increases with V_{dep}

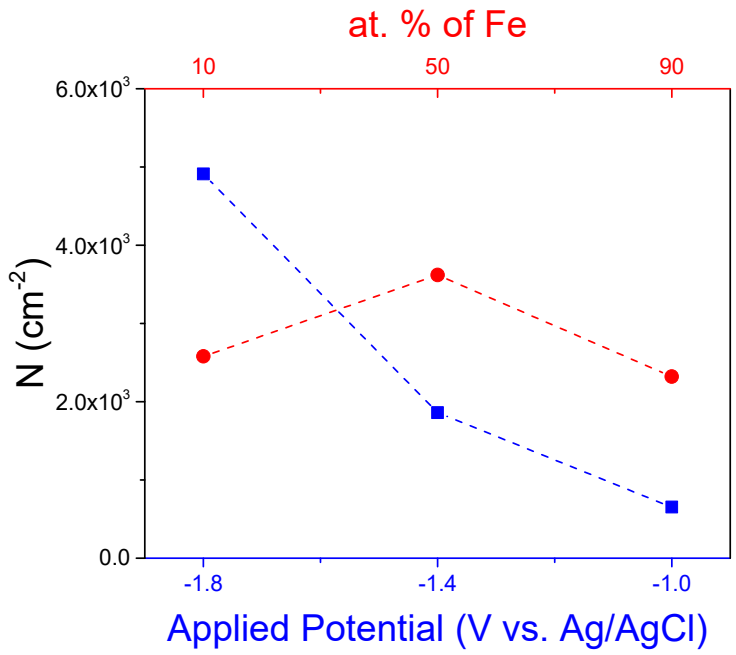

Figure S2. Number of nuclei vs. applied potential (blue squares) and vs. applied potential (red circles) for the electrodeposition of FeCo on Cu substrate.

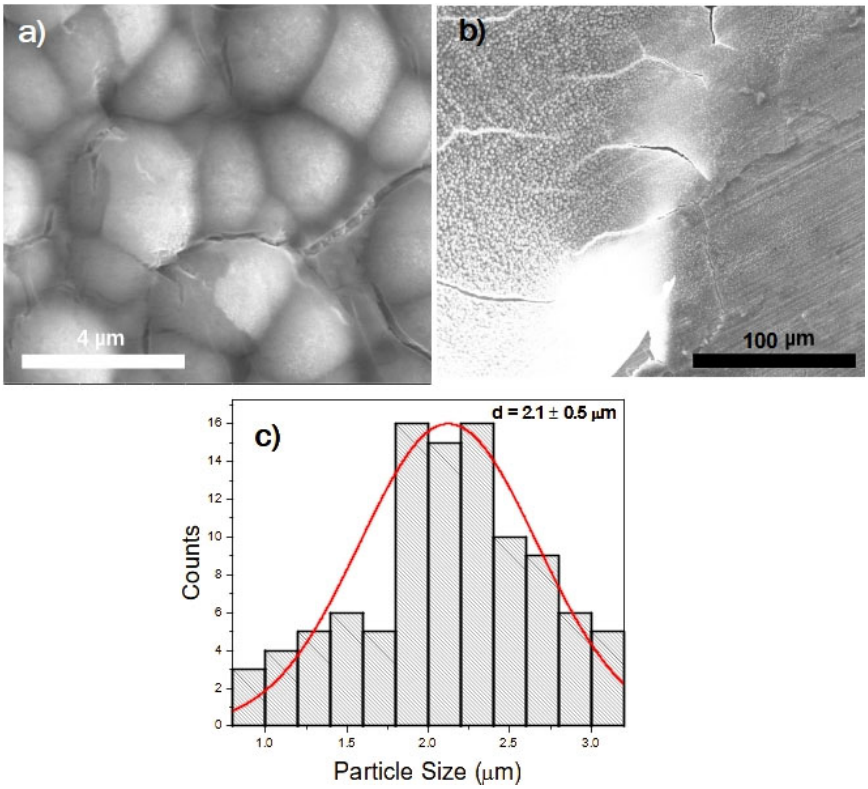

Figure S3. (a) and **(b)** Top view of the thin film electrodeposited on Cu substrate using the electrolyte 1 at electrodeposition potentials of - 1.4 V, and its corresponding **(c)** particle size distribution histogram.

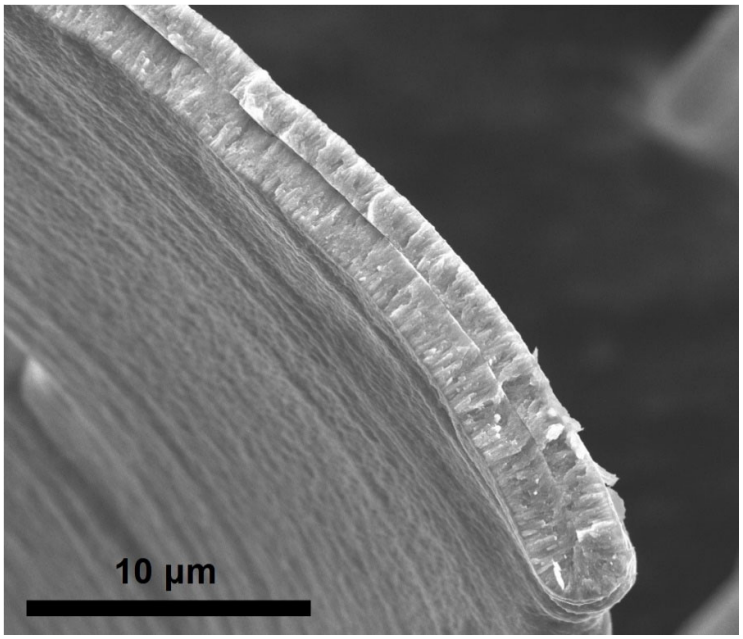

Figure S4. Cross-section SEM image (secondary electrons) of the thin film electrodeposited in Cu substrate using the electrolyte.